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EXAMINER

JONES, HUGH M

ART UNIT	PAPER NUMBER
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2123

DATE MAILED: 03/22/2002

Please find below and/or attached an Office communication concerning this application or proceeding.

Office Action Summary

Application No.
08/889,440

Applicant(s)
Takeuchi et al.

Examiner
Hugh Jones

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-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --

Period for Reply

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136 (a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If the period for reply specified above is less than thirty (30) days, a reply within the statutory minimum of thirty (30) days will be considered timely.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133).
- Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

Status

- 1) ☒ Responsive to communication(s) filed on 2/21 & 3/12/2002
- 2a) ☐ This action is **FINAL**. 2b) ☒ This action is non-final.
- 3) ☐ Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11; 453 O.G. 213.

Disposition of Claims

- 4) ☒ Claim(s) 1, 3-9, 11-20, and 22-31 is/are pending in the application.
- 4a) Of the above, claim(s) _____ is/are withdrawn from consideration.
- 5) ☐ Claim(s) _____ is/are allowed.
- 6) ☒ Claim(s) 1, 3-9, 11-20, and 22-31 is/are rejected.
- 7) ☐ Claim(s) _____ is/are objected to.
- 8) ☐ Claims _____ are subject to restriction and/or election requirement.

Application Papers

- 9) ☐ The specification is objected to by the Examiner.
- 10) ☐ The drawing(s) filed on _____ is/are objected to by the Examiner.
- 11) ☐ The proposed drawing correction filed on _____ is: a) ☐ approved b) ☐ disapproved.
- 12) ☐ The oath or declaration is objected to by the Examiner.

Priority under 35 U.S.C. § 119

- 13) ☐ Acknowledgement is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d).
- a) ☐ All b) ☐ Some* c) ☐ None of:
- ☐ Certified copies of the priority documents have been received.
 - ☐ Certified copies of the priority documents have been received in Application No. _____
 - ☐ Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).
- *See the attached detailed Office action for a list of the certified copies not received.
- 14) ☐ Acknowledgement is made of a claim for domestic priority under 35 U.S.C. § 119(e).

Attachment(s)

- 15) ☐ Notice of References Cited (PTO-892) 18) ☐ Interview Summary (PTO-413) Paper No(s). _____
- 16) ☐ Notice of Draftsperson's Patent Drawing Review (PTO-948) 19) ☐ Notice of Informal Patent Application (PTO-152)
- 17) ☐ Information Disclosure Statement(s) (PTO-1449) Paper No(s). _____ 20) ☐ Other: _____

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DETAILED ACTION

Claim Rejections - 35 USC § 112

1. The following is a quotation of the first paragraph of 35 U.S.C. 112:

The specification shall contain a written description of the invention, and of the manner and process of making and using it, in such full, clear, concise, and exact terms as to enable any person skilled in the art to which it pertains, or with which it is most nearly connected, to make and use the same and shall set forth the best mode contemplated by the inventor of carrying out his invention.

2. **Claims 1, 3-9, 11-20 and 22-31 are rejected under 35 U.S.C. 112, first paragraph, as containing subject matter which was not described in the specification in such a way as to enable one skilled in the art to which it pertains, or with which it is most nearly connected, to make and/or use the invention.**

3. As per claims directed at “formed particles” (claims 1-9 and 11-31), Examiner has reviewed pp. 31-33 of the specification. The specification only describes the composition of the combined particles; but, does not describe how the components of the formed (combined) particle are formed, as would be required to make and/or use the invention. A reader would have to reinvent the invention. The meaning is not clear. The claims recite “formed particles”. The particles therefore would have to be *combined* somehow during the course of the simulation. How is this done? It would constitute undue experimentation for a reader of any issued patent to make and/or use the claimed invention. Therefore, Examiner again repeats the request for a copy of Applicant’s software package so that Examiner can determine what constitutes “combined” or “formed”.

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4. Claims 1, 3-9, 11-20 and 22-31 are rejected under 35 U.S.C. 112, first paragraph, as containing subject matter which was not described in the specification in such a way as to reasonably convey to one skilled in the relevant art that the inventor(s), at the time the application was filed, had possession of the claimed invention.

5. As per claims directed at “formed particles” (claims 1-9 and 11-31), Examiner has reviewed pp. 31-33 of the specification. The specification only describes the composition of the combined particles; but, does not describe how the components of the formed (*combined*) particle are *formed*, as would be required to make and/or use the invention. A reader would have to reinvent the invention. The meaning is not clear. The claims recite “formed particles”. The particles therefore would have to be *combined* somehow during the course of the simulation. How is this done? Therefore, Examiner again repeats the request for a copy of Applicant’s software package so that Examiner can determine what constitutes “combined”.

Claim Interpretations

6. In general, the applicants are disclosing method and apparatus to simulate the trajectory of a “combined” or “formed” particle. *There is an abundance of publications concerning this topic as well as animated display of such simulations.* The Applicant has stated that the concept “*combined*” is of no consequence.

7. In so far as Applicants have stated (first paragraph, page 5, paper # 26) that limitations directed at “combining” are not to be given patentable weight, the Examiner interprets that

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reference to “absorbate” and “substrate” refer to intended use. There are no functional limitations which refer to “absorbate” and “substrate” other than *denotation* of the individual particles. A recitation of the intended use of the claimed invention must result in a structural difference between the claimed invention and the prior art in order to patentably distinguish the claimed invention from the prior art. If the prior art structure is capable of performing the intended use, then it meets the claim. In a claim drawn to a process of making, the intended use must result in a manipulative difference as compared to the prior art. See *In re Casey*, 152 USPQ 235 (CCPA 1967) and *In re Otto*, 136 USPQ 458, 459 (CCPA 1963). Therefore, any prior art which recites simulation of a trajectory of a “combined particle” is interpreted as reading on the claims.

8. The prior art rejections will be based on this interpretation of the specification and claims.

Claim Rejections - 35 USC § 103

9. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negated by the manner in which the invention was made.

10. **Claims 1, 3-9, 11-20, 22-31 are rejected under 35 U.S. C. 103 (a) as being unpatentable over (Misaka et al. *or* Baumann et al.) in view of the Examiner’s own experience and the taking of Official Notice.**

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11. Misaka et al. disclose a dry-etching process simulator wherein a surface reaction model is used to simulate topological evolutions by taking into account the existence of adsorbed radicals on the substrate surface. Baumann et al. disclose 3D modeling of sputtering using a mesoscopic hard-sphere Monte Carlo model. (see fig. 1 of Baumann et al.). Baumann et al. simulate the behavior of *clusters* as they interact with a substrate (note that the use of ion cluster beams and molecular beams for deposition and/or sputtering are well known techniques; this phenomena has also been simulated.). Both sets of inventors are concerned with the simulating the dynamics of particles which are interacting with a substrate during processing of the substrate. The claims are reviewed and the contributions by each inventor, as outlined above, are noted.

12. **As per claim 1, this is concerned with an apparatus for simulating phenomena of a particle formed of adsorbate particles and substrate particles**, Misaka et al.: figs. 1, 2, 3b, 4, 5 ("calculate fluxes"); col. 1, lines 35-68; col. 2, lines 29-34 and 49-59; col. 3, lines 16-68; col. 4, lines 50-65; Baumann et al.: pg. 4.4.1 and fig. 1), **comprising: a kinetic condition setting unit** (this is inherent in particle simulators such as monte Carlo simulators) **which sets information for defining a plurality of generation periods and a corresponding number of adsorbate particles to be generated during each generation period** (Misaka et al.: figs. 1, 2, 3b, 4, 5 ("calculate fluxes"); col. 1, lines 35-68; col. 2, lines 29-34 and 49-59; col. 3, lines 16-68; col. 4, lines 50-65; Baumann et al.: pg. 4.4.1 and fig. 1); **and**

a particle motion computing unit which generates the individual particles in accordance with the information set by the kinetic condition setting unit and computes

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motion of the generated adsorbate particles, to simulate phenomena of said particle formed of adsorbate and substrate particles, each adsorbate particle having a corresponding emission source (again, this is inherent in particle simulators such as Monte Carlo simulators; Misaka et al.: abstract; fig. 1,2; col. 2 lines 49-59 and 59-64; col. 3, lines 3-68; col. 4, lines 1-6; Baumann et al.: pg. 4.4.1);

for each adsorbate particle, the kinetic condition setting unit sets a region indicating a position of the corresponding emission source (Misaka et al.: fig. 1, # 15; also inherent in figs. 2, 7, 8b, 10; Baumann et al.: inherent in fig. 1), and

the particle motion computing unit generates each adsorbate particle in accordance with the position of the corresponding emission source (Misaka et al.: fig. 1, # 15; Baumann et al.: inherent in fig. 1).

13. **As per claim 3, this is concerned with an apparatus as in claim 1, wherein before generating the adsorbate particles, the particle motion computing unit generates the substrate particles** (this would seem to be inherent as well as obvious; why generate particles which are to interact with a target if the target is not there; Misaka et al.: figs. 1, 2, 3b, 4, 5, 7, 8b, 9, 10; col. 1, lines 35-68; col. 3, lines 16-68; col. 4, lines 50-65; Baumann et al.: fig. 1; inherent in fig. 2).

14. **As per claim 4, this is concerned with an apparatus as in claim 1, further comprising:**

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a display which allows a user to enter the information set by the kinetic condition setting unit (this is standard with respect to particle simulators in general. I have personally done this as it pertains to Monte Carlo simulations).

15. As per claim 5, this is concerned with an apparatus as in claim 1, wherein the kinetic condition setting unit sets information for generating the substrate particles (obviously, this information must be provided for each species; Misaka et al.: figs. 1, 2, 5 ("calculate fluxes"),- col. 2, lines 29-34 and 49-59, Baumann et al.: pg. 4.4.1).

16. As per claim 6, this is concerned with an apparatus as in claim 1, wherein each adsorbate particle is formed of atoms (Misaka et al.: fig. 1 ("radical"), fig. 2, fig. 4 (b,c,d); Baumann et al. - fig. 1; pg. 4.4.1) - this is also *inherent*;

the information set by the kinetic condition setting unit includes information indicating whether the atoms of a respective adsorbate particle are static against center of mass of the adsorbate particle (inherent in clusters); and

when the particle motion computing unit generates an adsorbate particle and the information set by the kinetic condition setting unit indicates that the atoms of the respective adsorbate particle are not static against the center of mass, the particle motion computing unit provides a random orientation to the atoms of the adsorbate particle (Official notice is taken that this physical phenomena and approximations so as to take it into account in simulations were well known in the art at the time of the invention. [see for example

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studies of ion attachment to electrodes submersed in salt solutions, studies of nucleation, or the motion of electrons around moving atoms or molecules]).

17. **As per claim 7, this is concerned with an apparatus as in claim 6, further comprising:**

a display which allows a user to enter the information set by the kinetic condition setting unit (this is standard with respect to particle simulators in general. I have personally done this as it pertains to Monte Carlo simulations).

18. **As per claim 8, this is concerned with an apparatus as in claim 1, wherein each adsorbate particle is formed of atoms** (Misaka et al.: fig. 1 ("radical"), fig. 2, fig. 4 (b,c,d); Baumann et al.: fig. 1; pg. 4.4.1),

the information set by the kinetic condition setting unit includes information indicating whether the smaller particles of a respective adsorbate particle are static against center of mass of the adsorbate particle (inherent in simulation of clusters), **and**

when the particle motion computing unit generates an adsorbate particle and the information set by the kinetic condition setting unit indicates that the atoms of the respective adsorbate particle are not static against the center of mass, the particle motion computing unit provides an initial velocity to the atoms of the adsorbate (I assume the applicant is talking about molecules here? [in which case the parts of the molecule interact with each other via vibrational modes, and thus are not bound]) **particle** (Official notice is taken that this physical phenomena and approximations so as to take it into account in simulations were

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well known in the art at the time of the invention. [see for example studies of ion attachment to electrodes submersed in salt solutions, studies of nucleation, or the motion of electrons around moving atoms or molecules]).

19. As per claim 9, this is concerned with an apparatus as in claim 1, wherein, when generating an adsorbate particle, the particle motion computing unit provides a random direction within a cone pointed at a substrate and being centered at a point of generation of center of mass velocity of the adsorbate particle (this is inherent in particle simulations in general, and in Monte Carlo simulations, in particular [see for example studies of gaseous discharges wherein an electron is emitted from a cathode or an electron is ejected from an atom due to collisional ionization]).

20. As per claim 11, this is concerned with an apparatus as in claim 1, further comprising a display which displays the information set by the kinetic condition setting unit (this is standard with respect to particle simulators in general. I have personally done this as it pertains to Monte Carlo simulations).

21. As per claim 12, this is concerned with an apparatus for simulating phenomena of a particle formed of adsorbate particles and substrate particles, each adsorbate particle having a corresponding emission source, the apparatus comprising:

an input device which allows a user to designate a region (this is standard with respect to particle simulators in general. I have seen done this as it pertains to Monte Carlo simulation [specifying the position of the cathode which is to eject electrons]; Misaka et al.: figs, 1, 5, 7, 8b,

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9, 10- Baumann et al.: inherent in fig. 1);

a kinetic condition setting unit which, for each adsorbate particle, sets the region designed by the user as a region indicating a position of the corresponding emission source (Misaka et al. fig. 1, # 15; Baumann et al.: inherent in fig. 1); and

a particle motion computing unit which generates the adsorbate particles in accordance with the position of the corresponding emission source as indicated by the region designated by the user and computes motion of the generated adsorbate particles, to simulate phenomena of said particle formed of adsorbate particles and substrate particles (Misaka et al.: fig. 1, # 15; fig. 5 - Baumann et al.: pg. 4.4.1).

22. **As per claim 13, this is concerned with an apparatus as in claim 12, wherein the input device is a display** (this is standard with respect to particle simulators in general. I have personally done this as it pertains to Monte Carlo simulations).

23. **As per claim 14, this is concerned with an apparatus as in claim 12, further comprising a display which displays the information set by the kinetic condition setting unit** (this is standard with respect to particle simulators in general. I have personally done this as it pertains to Monte Carlo simulations).

24. **As per claim 15, this is concerned with an apparatus as in claim 14, wherein the display shows the adsorbate particles generated by the particle motion computing unit and indicates the motion computed by the particle motion computing unit** (this is standard in the

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art; I have seen this type of display at conferences [Official notice is taken that this feature was well known in the art at the time of the invention.).

25. As per claim 16, this is concerned with an apparatus for simulating phenomena of a particle formed of adsorbate particles and substrate particles, comprising:

a kinetic condition setting unit (this is inherent in particle simulators such as monte Carlo simulators) **which sets information for defining kinetic conditions of the adsorbate particles** (Misaka et al.: figs. 1, 2, 5 ("calculate fluxes"); col. 2, lines 29-34 and 49-59; Baumann et al.: pg. 4.4.1); **and**

a particle motion computing unit which generates the adsorbate particles in accordance with the information set by the kinetic condition setting unit and the position of the corresponding emission source and computes motion of the generated adsorbate particles, to simulate phenomena of said particle formed of adsorbate particles and substrate particles, each adsorbate particle having a corresponding emission source (again, this is inherent in particle simulators such as Monte Carlo simulators; Misaka et al.: abstract; fig. 1, 2 col. 2 lines 49-59 and 59-64; col. 3, lines 3-68; col. 4, lines 1-6; Baumann et al.: pg. 4.4.1).

26. As per claim 17, this is concerned with an apparatus as in claim 16, wherein

the adsorbate particles move towards the substrate particles (Misaka et al. - fig. 1, 2, 3b; Baumann et al.: fig. 1),

the kinetic condition setting unit sets a region for defining an initial position of the adsorbate particles (Misaka et al.: figs. 1, 5; Baumann et al.: inherent on pg. 4.4.1),

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the apparatus further comprises a display which displays the relationship between the region set by the kinetic condition setting unit and a region indicating a position of a substrate particle forming said particle formed of adsorbate particles and substrate particles (this is standard in the art; I have seen this type of display at conferences [Official notice is taken that this feature was well known in the art at the time of the invention.]).

27. **As per claim 18, this is concerned with an apparatus as in claim 17, wherein**

the kinetic condition setting unit sets information for providing a direction of velocity to the adsorbate particles (Misaka et al.: fig. 1 # 15; Baumann et al.: inherent on pg. 4.4.1), and

the display shows the direction of velocity with respect to the region set by the kinetic condition setting unit and the region indicating the position of a respective substrate particle (this is standard in the art; I have seen this type of display at conferences [Official notice is taken that this feature was well known in the art at the time of the invention.]).

28. **As per claim 19, this is concerned with an apparatus as in claim 16, further comprising a display which displays the information set by the kinetic condition setting unit** (this is standard with respect to particle simulators in general. I have personally done this as it pertains to Monte Carlo simulations).

29. **As per claim 20, this is concerned with a computer-implemented method for simulating phenomena of a particle formed of adsorbate particles and substrate particles,**

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each adsorbate particles having a corresponding emission source, the method comprising the steps of:

setting information for defining a plurality of generation periods and a corresponding number of adsorbate particles to be generated during each generation period (Misaka et al.: fig. 1, # 15; Baumann et al.: inherent on pg. 4.4.1);

generating the adsorbate particles in accordance with the information set in the setting step and the position of the corresponding emission source (Misaka et al.: fig. 1, # 15; Baumann et al.: inherent on pg. 4.4.1), **and**

computing motion of the generated adsorbate particles, to simulate phenomena of said particle formed of adsorbate particles and substrate particles (again, this is inherent in particle simulators such as Monte Carlo simulators, Misaka et al.: abstract; fig. 1, 2; col. 2 lines 49-59 and 59-64; col. 3, lines 3-68; col. 4, lines 1-6; Baumann et al.: pg. 4.4.1).

30. As per claim 22, this is concerned with a computer-implemented method for simulating phenomena of a particle formed of adsorbate particles and substrate particles, each adsorbate particle having a corresponding emission source, the method comprising the steps of

setting, for each adsorbate particle, a region indicating a position of the corresponding emission source (this is standard with respect to particle simulators in general. I have seen done this as it pertains to Monte Carlo simulation [specifying the position of the

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cathode which is to eject electrons]; Misaka et al.: figs. 1, 5, 7, 8b, 9, 10; Baumann et al.:

inherent on pg. 4.4.1),

generating the adsorbate particles in accordance with the position of the corresponding emission source as indicated by the region set in the setting step (Misaka et al.: fig. 1, # 15; Baumann et al.: inherent on pg. 4.4.1);

computing motion of the generated adsorbate particles, to simulate phenomena of the combined particle (Misaka et al.: fig. 1, # 15; Baumann et al.: pg. 4.4. 1); and

simulating phenomena of said particle formed of adsorbate particles and substrate particles in accordance with the computed motion.

31. As per claim 23, this is concerned with a method for simulating phenomena of a particle formed of adsorbate particles and substrate particles, said method comprising:

setting information for defining kinetic conditions of the adsorbate particles;

displaying the set information (Misaka et al.: figs. 1, 2, 5 ("calculate fluxes"); col. 2, lines 29-34 and 49-59; Baumann et al.: inherent on pg. 4.4.1);

generating the adsorbate particles in accordance with the set information and the positions of the corresponding emission sources (again, this is inherent in particle simulators such as Monte Carlo simulators; Misaka et al.: abstract; fig. 1,2; col. 2 lines 49-59 and 59-64; col. 3, lines 3-68; col. 4, lines 1-6; Baumann et al.: inherent on pg. 4.4.1); and

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computing motion of the generated adsorbate particles, to simulate phenomena of said particle formed of adsorbate particles and substrate particles, each adsorbate particle having a corresponding emission source (again, this is inherent in particle simulators such as Monte Carlo simulators; Misaka et al.: abstract; fig. 1, 2; col. 2 lines 49-59 and 59-64; col. 3, lines 3-68; col. 4, lines 1-6; Baumann et al.: pg. 4.4.1).

32. As per claim 24, this is concerned with an apparatus for simulating phenomena of a particle formed with adsorbate particles, comprising:

a kinetic condition setting unit (this is inherent in particle simulators such as monte Carlo simulators) **which sets information for defining kinetic conditions of the adsorbate particles** (Misaka et al.: figs. 1, 2, 5 ("calculate fluxes"); col. 2, lines 29-34 and 49-59; Baumann et al.: inherent on pg. 4.4.1), and

a particle motion computing unit which generates the adsorbate particles in accordance with the information set by the kinetic condition setting unit and computes motion of the generated adsorbate particles, to simulate phenomena of said particle formed with adsorbate particles, each adsorbate particle having a corresponding emission source (again, this is inherent in particle simulators such as Monte Carlo simulators; Misaka et al.: abstract; fig. 1,2; col. 2 lines 49-59 and 59-64; col. 3, lines 3-68; col. 4, lines 1-6; Baumann et al.: pg. 4.4.1);

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for each adsorbate particle, the kinetic condition setting unit sets a region indicating a position of the corresponding emission source (Misaka et al.: fig. 1, # 15; also inherent in figs. 2, 7, 8b, 10; Baumann et al.: inherent on pg. 4.4.1), and

the particle motion computing unit generates each adsorbate particle in accordance with the position of the corresponding emission source as indicated by the region set by the kinetic condition setting unit (Misaka et al.: fig. 1, # 15; Baumann et al.: pg. 4.4.1).

33. As per claim 25, this is concerned with an apparatus as in claim 24, wherein the information set by the kinetic condition setting unit (this is inherent in particle simulators such as Monte Carlo simulators) defines a plurality of generation periods and a corresponding number of adsorbate particles to be generated during each generation period by the particle motion computing unit (Misaka et al.: figs. 1, 2, 5 ("calculate fluxes"); col. 2, lines 29-34 and 49-59; Baumann et al.: inherent on pg. 4.4.1).

34. As per claim 26, this is concerned with an apparatus as in claim 24, wherein said particle formed with adsorbate particles is formed with both adsorbate particles and substrate particles,

the information set by the kinetic condition setting unit includes information for defining kinetic conditions of the substrate particles (Misaka et al.: figs. 1, 2, 5 ("calculate fluxes"); col. 2, lines 29-34 and 49-59; Baumann et al.: inherent on pg. 4.4.1); and

the particle motion computing unit generates the substrate particles before generating the adsorbate particles (this would seem to be obvious; why generate particles

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which are to interact with a target if the target is not there; Misaka et al.: figs. 1, 2, 4, 5, 7, 8b, 9, 10; Baumann et al.: pg. 4.4.1).

35. As per claim 27, this is concerned with an apparatus as in claim 24, wherein

said particle with adsorbate particles is formed with both adsorbate particles and substrate particles,

each substrate particle includes a fixed particle and a temperature control particle
(Baumann et al.: temperatue: fig. 6)),

the information set by the kinetic condition setting unit includes information for defining kinetic conditions of the fixed particle and the temperature control particle
(Misaka et al.: figs. 1, 2, 5 ("calculate fluxes"); col. 2, lines 29-34 and 49-59; Baumann et al.: inherent on pg. 4.4.1), **and**

the particle motion computing unit generates the fixed particle and the temperature control particle of each substrate particle in accordance with the information set by the kinetic condition setting unit (again, this is inherent in particle simulators such as Monte Carlo simulators; Misaka et al.: abstract; fig. 1,2; col. 2 lines 49-59 and 59-64; col. 3, lines 3-68; col. 4, lines 1-6; Baumann et al.: inherent on pg. 4.4.1).

36. As per claim 28, this is concerned with an apparatus as in claim 24, further

comprising a display which displays the information set by the kinetic condition setting unit (this is standard with respect to particle simulators in general. I have personally done this as it pertains to Monte Carlo simulations).

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37. As per claim 29, this is concerned with an apparatus as in claim 24, wherein each adsorbate particle includes a plurality of atoms (Misaka et al.: fig. 1 ("radical"), fig. 2, fig. 4 (b,c,d); Baumann et al. fig. 1);

the information set by the kinetic condition setting unit includes information indicating whether the atoms of a respective adsorbate particle are static against center of mass of the adsorbate particle (inherent in simulation of clusters); and

when the particle motion computing unit generates an adsorbate article and the information set by the kinetic condition setting unit indicates that the atoms of the respective adsorbate particle are not static against center of mass, the particle motion computing unit provides a random orientation to the atoms of the adsorbate particle

(Official notice is taken that this physical phenomena and approximations so as to take it into account in simulations were well known in the art at the time of the invention. [see for example studies of ion attachment to electrodes submersed in salt solutions, studies of nucleation, or the motion of electrons around moving atoms or molecules]).

38. As per claim 30, this is concerned with an apparatus as in claim 29, wherein, when the particle motion computing unit generates an adsorbate particle and the information set by the kinetic condition setting unit indicates that the atoms of the respective adsorbate particle are not fixed against center of mass, the particle motion computing unit provides an initial velocity to the atoms of the adsorbate particle (Official notice is taken that this physical phenomena and approximations so as to take it into account in simulations were well

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known in the art at the time of the invention. [see for example studies of ion attachment to electrodes submersed in salt solutions, studies of nucleation, or the motion of electrons around moving atoms or molecules]).

39. As per claim 31, this is concerned with an apparatus as in claim 24, wherein, when generating an adsorbate particle, the particle motion computing unit provides a random direction within a cone pointed at a substrate and being centered at a point of generation of center of mass velocity of the adsorbate particle (Official notice is taken that this physical phenomena and approximations so as to take it into account in simulations were well known in the art at the time of the invention. [see for example studies of ion attachment to electrodes submersed in salt solutions, studies of nucleation, or the motion of electrons around moving atoms or molecules]).

40. Claims 1, 3-9, 11-20, 22-26 and 28-31 are rejected under 35 U.S.C. 103(a) as being unpatentable over (Yamada et al. *or* Misaka et al. *or* Baumann et al. *or* Husinsky et al.) in view of (Kinema/SIM or Reeves or Cohen).

41. Yamada et al. discloses details of a Monte Carlo simulation of sputtering. See entire disclosure. Especially note fig. 1-3.

42. Misaka et al. disclose a dry-etching process simulator wherein a surface reaction model is used to simulate topological evolutions by taking into account the existence of adsorbed radicals on the substrate surface. See figs. 1, 2, 3b, 4, 5 ("calculate fluxes"); col. 1, lines 35-68; col. 2, lines 29-34 and 49-59; col. 3, lines 16-68; col. 4, lines 50-65.

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43. Baumann et al. disclose 3D modeling of sputtering using a mesoscopic hard-sphere Monte Carlo model. (see fig. 1 of Baumann et al.). Baumann et al. simulate the behavior of *clusters* as they interact with a substrate (note that the use of ion cluster beams and molecular beams for deposition and/or sputtering are well known techniques; this phenomena has also been simulated.). See pg. 4.4.1 and fig. 1-2.
44. Husinsky et al. disclose "*Fundamental aspects of SNMS for thin film characterization: Experimental studies and computer simulations.*" They further disclose that the idea of secondary neutral mass spectroscopy (SNMS) as a tool for surface analysis dates back to the early 1970s. Recently, due to the development of new and effective post ionization tools, i.e. lasers, this method has become an interesting alternative to more conventional methods for various applications in surface analysis, as for instance depth profiling or characterization of thin films. SNMS, in general, involves a more complicated apparatus than other techniques, due to the additional post-ionizing stage. However, in the last few years it has been demonstrated by many groups that for several situations SNMS offers substantial advantages as compared with conventional methods, in particular secondary ion mass spectrometry. In this paper they evaluate the current situation of SNMS, in particular laser-SNMS, for applications related to the field of thin film research. On behalf of experimental studies and *computer simulations of various phenomena related to SNMS* they show the possibilities, advantages and also problems associated with the method. See section 4 (sputtering) including section 4.1 (sputtered flux - fig.

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4, 9 and 16 - showing combined particles); section 4.3 (computer simulation of sputtering) and section 4.4 (cluster emission).

45. (Yamada et al. *or* Misaka et al. *or* Baumann et al. *or* Husinsky et al.) discloses all claim limitations except for a teaching animation of the simulation. (Kinema/SIM *or* Reeves *or* Cohen) teach that it was obvious and well known to one of ordinary skill in the art at the time of the invention to animate simulations of physical processes. (Kinema/SIM *or* Reeves *or* Cohen) provide details about animations of particles. The teachings of (Kinema/SIM *or* Reeves *or* Cohen) are subsequently presented.

46. Kinema/SIM is a software tool that presents a simulation space for particle behavior where you can construct and animate complex physical phenomena. See entire disclosure. A number of features are subsequently listed for Applicant's benefit.

- Examples of the graphical interface are shown on pp. 1-8 to 1-9;
- the "particle window" is shown on pg. 2-7; here the particle parameters can be altered;
- "Lifetime" defines the particle lifetime (pg. 2-9);
- "particle geometry" is discussed on pg. 2-11;
- "coordinate systems" are discussed on pg. 3-3;
- entering particle parameter values via slider buttons (pg. 3-10);
- probability functions for particle speed, lifetime, emission angles (pg. 3-11);
- other relevant temporal parameters (pg. 3-16);
- GUI simulation controls (pg. 5-2);

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- statistical features (ie., group behavior - pg. 5-3);
- particles, obstacles (pg. 5-5);
- details about simulation parameter values including source rate, display, particle interactions and emission sources (chapter 6);
- range of interactions between particles (pg. 6-3);
- source rate (pg. 6-4);
- a combined particle (pg. 6-5), wherein

"The Euler mode, on the other hand, calculates forces more globally and therefore has the advantage of maintaining simulation speed. It calculates only one force per cell at time t, which is applied to all particles in the cell. ...";

- Chapter 7 discloses "Particles";
- particle coupling (pg. 7-1);
- particle examples (pg. 7-1), wherein

"Particles are the key element in Kinema/SIM simulations. They are point objects that can represent a broad range of physical and image characteristics such as mass, charge, color, motion and geometry. In your simulation, particles can represent a diversity of real or image objects such as quantum physics particles, gas molecules, aerosol droplets, bacteria, fluid flow, dust, rain, snow, sand, or pixels of images. The possibilities are as numerous as the phenomena of reality and creative animation ...

... Particles are emitted into the simulation via sources which can be visible or invisible points or geometric objects positioned in simulation space. ...";

- particles parameter window (pg. 7-3 to 7-4);

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- "Sigma", a parameter related to particle-particle interactions (pp. 7-13 to 7-14);
- decay particles (pg. 7-21);
- particle coupling (pp. 7-22 to 7-23);
- Chapter 8 (source parameters);
- sources (pg. 8-1), wherein

"Sources are origins that emit particles into the simulation, and all particles must enter the simulation via a source. Sources can be points or have spatial geometry which you can choose to see or hide in simulation space. You can define as many sources as you like for a system, but each source is restricted to emit only one particle type. (If you want to have more than one particle type originate from the same position, you can superimpose sources at the point. ...

... In the source window you assign a particle type to the source and then define the rate and speed of the particles along with their spread angle into the simulation. ..."

The "spread angle" is Applicant's "cone".;

- source window (pg. 8-3);
- source rate (pg. 8-4);
- **Spread** (pg. 8-5);
- speed (pg. 8-6);
- source position (pg. 8-10);
- display (pg. 8-11);
- geometry (pg. 8-13);
- particle emission and geometry (pp. 8-15 to 8-16);

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- particle generation (pp. 8-16 to 8-17);
- Chapter 9 “Obstacles”;
- Chapter 13, “electric fields”;
- Chapter 15, “particle events”;
- elastic and inelastic particle collisions (pp. 15-1 to 15-2);

47. Reeves discloses animation of particle behavior and discloses the concept of combined particle. On page 91,

“First, an object is represented not by a set of primitive surface elements, such as polygons or patches, that define its boundary, but as clouds of primitive particles that define its volume.”

Section 2.1 discloses particle generation. Section 2.2 discloses:

“For each new particle generated, the particle system must determine values for the following attributes:

- (1) initial position,*
- (2) initial velocity (both speed and direction),*
- (3) initial size,*
- (4) initial color,*
- (5) initial transparency,*
- (6) shape,*
- (7) lifetime.*

Section 2.3 discloses particle dynamics.

48. Cohen discloses *“Computer animations, quantum mechanics and elementary particles.”*

See entire disclosure. The following is from pg. 165;

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"In a typical animation, starting from a small number of virtual particles, the number tends to increase as a function of time, signaling the deviation from the physical states. A physical particle contains a cloud of finite size of virtual particles. The animation actually allows us to see the formation of such clouds. It is rather amusing to identify dressed objects manifesting collective behavior, and then analyze the space renormalization group of the clouds by zooming in."

On page 166, the following is found:

The visualization "dictionary" developed for computer animations of quantum systems can be applied to any process following the rules of one or several of Nature's fundamental interactions. Animation of various atomic and subatomic phenomena such as electron orbitals, particle collisions, radioactive decay, fusion, fission, etc. are therefore feasible and instructive."

49. **Claims 1, 3-9, 11-20 and 22-31 are rejected under 35 U.S.C. 103(a) as being unpatentable over [Ohira et al. (Applicant - Applicant's IDS).] in view of (Kinema/SIM or Reeves or Cohen).**

50. Ohira et al. discloses details of a Molecular-dynamics simulation of sputtering. See: abstract; pg. 2 (Theoretical Methods) and especially fig. 1.

51. [Ohira et al.] discloses all claim limitations (see **fig. 1 - temperature control particles**) except for a teaching of animation of the simulation. (Kinema/SIM or Reeves or Cohen) teach that it was obvious and well known to one of ordinary skill in the art at the time of the invention to animate simulations of physical processes. (Kinema/SIM or Reeves or Cohen) provide details about animations of particles. The teachings of (Kinema/SIM or Reeves or Cohen) were presented earlier.

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Response to Arguments

52. Applicant's arguments filed 2/21/2002 have been fully considered but they are not persuasive.

Regarding the 112(1) rejections (page 8, paper 29):

53. As per claims directed at "formed *particles*", Examiner has reviewed pp. 31-33 of the specification. The specification only describes the possible composition of the combined particles; but, does not describe how the components of the combined particle are combined or formed. The meaning is not clear especially in light of Applicant's various comments in paper # 9 as well as those provided in papers # 16 and # 19. The matter is still not resolved in paper # 26 (pp. 4-5) or paper # 29. Therefore, Examiner again repeats the request for a copy of Applicant's software package so that Examiner can determine what constitutes "combined" or "formed". Applicants are reminded that the claims were rejected under 35 U.S.C. 112, first paragraph, because *they contain subject matter which was not described in the specification in such a way as to enable one skilled in the art to which it pertains, or with which it is most nearly connected, to make and/or use the invention*. In response, Applicants simply asserts that it does not matter how the particles are combined. How could *one skilled in the art to which it pertains, or with which it is most nearly connected, to make and/or use the invention*, namely combined particles, if the *subject matter was not adequately described in the specification*?

54. Applicants have also argued (paragraph 4, page 5, paper # 26 - referring to the request for Applicant's computer code) that "...*complying with such a request would be a very heavy,*

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expensive burden on the Applicants.” The Examiner respectfully submits that the existence of such lengthy computer code suggests that there is much disclosure lacking in the specification. However, the issue could easily be resolved (and compact prosecution facilitated) by a review of said code.

55. Applicants have stated that the concept “*combined*” is of no consequence. However, the particles would have to be “combined” in some fashion during the simulation. The Examiner respectfully submits that it would constitute *undo experimentation* to determine how to “combine” the particles. Furthermore, in so far as Applicants have stated (first paragraph, page 5, paper # 26) that limitations directed at “combining” are not to be given patentable weight, the Examiner interprets that reference to “absorbate” and “substrate” refer to intended use. There are no functional limitations which refer to “absorbate” and “substrate” other than *denotation* of the individual particles. A recitation of the intended use of the claimed invention must result in a structural difference between the claimed invention and the prior art in order to patentably distinguish the claimed invention from the prior art. If the prior art structure is capable of performing the intended use, then it meets the claim. In a claim drawn to a process of making, the intended use must result in a manipulative difference as compared to the prior art. See *In re Casey*, 152 USPQ 235 (CCPA 1967) and *In re Otto*, 136 USPQ 458, 459 (CCPA 1963). As stated in paper # 27:

“Therefore, any prior art which recites simulation of a trajectory of a
“combined particle” is interpreted as reading on the claims. *The Examiner will*

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remove the 112(1) rejections in the event that Applicants agree with the above interpretations."

Applicants have not responded to the above.

56. *Furthermore, it is noted that Applicants abandoned the application after notice of allowance, since Applicants disagreed with Examiner's interpretation regarding "interacting" (which of course defines how the particles are combined or combined). Since this point is so important (page 13, paper # 12), the Examiner requires an explanation of how a reader of any issued patent could make and/or used the claimed invention absent the teaching of "combined" or "formed".*

Regarding the 112(2) rejections (page 8, paper 29):

57. The 112(2) rejection has been withdrawn in response to amendment.

Regarding the 103 rejections (pages 8-10, paper 29):

58. The Examiner notes Applicant's arguments pertaining to the prior art rejections. In general, Applicants appear to have again *mischaracterized* the prior art in spite of numerous attempts by the Examiner to correct the record. The Examiner can only continue to repeat the rejections.

59. In response to applicant's arguments against the references individually (pp. 8-10, paper # 29), one cannot show nonobviousness by attacking references individually where the rejections

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are based on combinations of references. See *In re Keller*, 642 F.2d 413, 208 USPQ 871 (CCPA 1981); *In re Merck & Co.*, 800 F.2d 1091, 231 USPQ 375 (Fed. Cir. 1986). The Examiner *repeats* the above in response to Applicant's continued "piecemeal" analysis of the 103 rejections. **These arguments apply to all of Applicant's arguments as they relate to the 103 rejections.**

60. As per emission sources - these are inherent in particle simulators. As per "*adsorbate*" and "*substrate*", please see the art rejections and the discussion, earlier relating to *intended use*.

61. Applicants have stated that the concept "*combined*" is of no consequence. In so far as Applicants have stated (first paragraph, page 5, paper # 26) that limitations directed at "combining" (which means the same as "*formed*", in the context of Applicant's invention) are not to be given patentable weight, the Examiner interprets that reference to "absorbate" and "substrate" refer to intended use. There are no functional limitations which refer to "absorbate" and "substrate" other than *denotation* of the individual particles. A recitation of the intended use of the claimed invention must result in a structural difference between the claimed invention and the prior art in order to patentably distinguish the claimed invention from the prior art. If the prior art structure is capable of performing the intended use, then it meets the claim. In a claim drawn to a process of making, the intended use must result in a manipulative difference as compared to the prior art. See *In re Casey*, 152 USPQ 235 (CCPA 1967) and *In re Otto*, 136 USPQ 458, 459 (CCPA 1963). Therefore, any prior art which recites simulation of a trajectory of a "combined particle" is interpreted as reading on the claims.

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62. Applicant's characterization of the teachings of Baumann and Misaka again trivializes and misstates their inventions - *Again*, please refer to the detailed rejections as well as the teachings. For example, the characterization of the Baumann teaching as "...incoming spheres ..." again ignores the teaching of a simulation of Sputtering - *that which Applicant is attempting to claim. Page 4.4.2 of Baumann discloses molecular dynamic simulation (simulation of trajectories)*. As per Misaka, see fig. 2; col. 9, line 65 to col. 10, line 9, wherein trajectories are discussed. *In either Baumann or Misaka, it is inherent that a source must exist for each particle.*

63. Applicants; characterization of the teaching of Reeves trivializes and mischaracterizes the invention - Please refer to the detailed rejections as well as the teachings. *For example, and Examiner would again like to point out - reference to "fuzzy" is irrelevant and has absolutely nothing to do with the issues at hand.* As recited in the last four Official Office Actions: "Reeves discloses animation of particle behavior and discloses the concept of combined particle. On page 91,

"First, an object is represented not by a set of primitive surface elements, such as polygons or patches, that define its boundary, but as clouds of primitive particles that define its volume."

Section 2.1 discloses particle generation. Section 2.2 discloses:

"For each new particle generated, the particle system must determine values for the following attributes:

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- (1) **initial position.**
- (2) **initial velocity (both speed and direction).**
- (3) *initial size,*
- (4) *initial color,*
- (5) *initial transparency,*
- (6) *shape,*
- (7) *lifetime.*

Section 2.3 discloses particle dynamics.”

Please note the bold-faced portions - **which define particle sources.**

64. As recited in the last **four** Official Office Actions, “Cohen discloses “*Computer animations, quantum mechanics and elementary particles.*” See entire disclosure. The following is from pg. 165;

“In a typical animation, starting from a small number of virtual particles, the number tends to increase as a function of time, signaling the deviation from the physical states. A physical particle contains a cloud of finite size of virtual particles. The animation actually allows us to see the formation of such clouds. It is rather amusing to identify dressed objects manifesting collective behavior, and then analyze the space renormalization group of the clouds by zooming in.”

On page 166, the following is found:

The visualization “dictionary” developed for computer animations of quantum systems can be applied to any process following the rules of one or several of Nature’s fundamental interactions. Animation of various atomic and subatomic

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phenomena such as electron orbitals, particle collisions, radioactive decay, fusion, fission, etc. are therefore feasible and instructive.”

Cohen discloses particle sources.

65. As recited in the last four Official Office Actions: “Kinema/SIM is a software tool that presents a simulation space for particle behavior where you can construct and animate complex physical phenomena. See entire disclosure. A number of features are subsequently listed for Applicant’s benefit.

- Examples of the graphical interface are shown on pp. 1-8 to 1-9;
- the “particle window” is shown on pg. 2-7; here the particle parameters can be altered;
- “Lifetime” defines the particle lifetime (pg. 2-9);
- “particle geometry” is discussed on pg. 2-11;
- “coordinate systems” are discussed on pg. 3-3;
- entering particle parameter values via slider buttons (pg. 3-10);
- probability functions for particle speed, lifetime, emission angles (pg. 3-11);
- other relevant temporal parameters (pg. 3-16);
- GUI simulation controls (pg. 5-2);
- statistical features (ie., group behavior - pg. 5-3);
- particles, obstacles (pg. 5-5);

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- details about simulation parameter values including source rate, display, particle interactions and emission sources (chapter 6);
- range of interactions between particles (pg. 6-3);
- source rate (pg. 6-4);
- a combined particle (pg. 6-5), wherein

"The Euler mode, on the other hand, calculates forces more globally and therefore has the advantage of maintaining simulation speed. It calculates only one force per cell at time t, which is applied to all particles in the cell. ...";

- Chapter 7 discloses "Particles";
- particle coupling (pg. 7-1);
- particle examples (pg. 7-1), wherein

"Particles are the key element in Kinema/SIM simulations. They are point objects that can represent a broad range of physical and image characteristics such as mass, charge, color, motion and geometry. In your simulation, particles can represent a diversity of real or image objects such as quantum physics particles, gas molecules, aerosol droplets, bacteria, fluid flow, dust, rain, snow, sand, or pixels of images. The possibilities are as numerous as the phenomena of reality and creative animation ...

... Particles are emitted into the simulation via sources which can be visible or invisible points or geometric objects positioned in simulation space. ...";

- particles parameter window (pg. 7-3 to 7-4);
- "Sigma", a parameter related to particle-particle interactions (pp. 7-13 to 7-14);
- decay particles (pg. 7-21);

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- particle coupling (pp. 7-22 to 7-23);
- Chapter 8 (source parameters);
- sources (pg. 8-1), wherein

"Sources are origins that emit particles into the simulation, and all particles must enter the simulation via a source. Sources can be points or have spatial geometry which you can choose to see or hide in simulation space. You can define as many sources as you like for a system, but each source is restricted to emit only one particle type. (If you want to have more than one particle type originate from the same position, you can superimpose sources at the point. ...

... In the source window you assign a particle type to the source and then define the rate and speed of the particles along with their spread angle into the simulation. ..."

The "spread angle" is Applicant's "cone".;

- source window (pg. 8-3);
- source rate (pg. 8-4);
- **Spread** (pg. 8-5);
- speed (pg. 8-6);
- **source position** (pg. 8-10);
- display (pg. 8-11);
- geometry (pg. 8-13);

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- particle emission and geometry (pp. 8-15 to 8-16);
- particle generation (pp. 8-16 to 8-17);
- Chapter 9 “Obstacles”;
- Chapter 13, “electric fields”;
- Chapter 15, “particle events”;
- elastic and inelastic particle collisions (pp. 15-1 to 15-2)”.

Kinema/Sim discloses particle sources. Applicants’s response is simply not credible.

Examiner can only *again repeat* the request that Applicants please review the art rejection and the art.

Conclusion

66. The prior art made previously of record and not relied upon is considered pertinent to applicant's disclosure.

- **Bouvier et al.:** “*From crowd simulation to airbag deployment: particle systems, a new paradigm of simulation.*” This publication discloses details concerning the *Kinema/Sim* software package. The reference apparently does not qualify as prior art since the date of publication is 1/97. However, the reference compactly summarizes the matter disclosed in the Kinema/Sim manual and is provided for Applicant’s benefit. See particularly: Section 1, including: section 1.1 (*Introduction and Objectives*), section 1.2 (*Particle Systems*), sections 1.2.1 and 1.2.2; Section 2 (*Particle Systems*), especially section 2.2, wherein:

“A particle system is defined by:

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The description of the **particle types**,
The **particle sources which generate the sources**,
The **3D geometry, including obstacles**,
The **evolution of these particles** within the system”;

section 2.2.2 wherein the particle object is defined, including, among others:

“its **values for interactions with surfaces** (stick, bounce, penetrate, transform, etc),
its **visualization parameters: color, size, transparency, trail memory, geometry**”;

section 2.2.2 (***Generation of Particles***), wherein;

“Generating particles implies the description of an initial state for the system, by defining particles of different types, with imposed positions and velocities. During the simulation, the interaction of these particles with the system will change these initial values, but the **user will have the possibility to create new particles**, with defined position and velocities.

The particles are generated by sources. Sources are geometric entities emitting only one type of particle. They are defined by:

Their **position in the space and their dimension**,
Their **size and geometry**,
Their **rate of emission as a function of time**,
Their **direction of emission: a given vector, a local normal to a surface, or a given trajectory**”;

section 2.2.3 (***Evolution of particles***); section 2.2.5 (***Advantages of the Kinema approach to particle systems***), wherein, among other things:

“the system can:
handle **collisions of particles with objects, surfaces and with other particles**,
manage the position of sources and emission parameters (rate, direction, speed)”;

section 3.6 (***visualization***); and section 5 (***Further simulations under development***), wherein,

“Obstacles and source management facilitates enable us to model different kinds of phantoms (scattering environment shapes and radioactive spatial distributions). ...”

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- Ohta (U. S. Patent 5,751,607, Method (Sputter Deposition Simulation by Inverse Trajectory Calculation, 1998) discloses the use of Monte Carlo techniques as it pertains to the simulation of sputtering. [of record]

- Jones et al., "Monte Carlo Investigation of Electron-Impact Ionization in Liquid Xenon," Phys. Rev. B., 48, 9382-9387, 1993 teaches the use of Monte Carlo techniques as it pertains to electron transport in condensed media; references are provided to more detailed descriptions of Monte Carlo techniques. [of record]

- Takagi, "Development of New Materials by Ionized-Cluster Beam Technique," Mat. Res. Soc. Symp. Proc., 27, 501-511, 1984 discloses ion beam clusters ("combined particles") and its relation to deposition. [of record]

- Cornell Theory Center (1996) discloses an animated simulation of the dynamic failure of 3D solids under tension at the atomistic level using classical molecular dynamics and system sizes from 10 to more than 100 million atoms. [of record]

- XSIMBAD (1996) discloses a Monte Carlo simulation software package. A condition setting user template is shown on pp 3-4; animated simulation results are shown on pp. 5 and 11-12, graphical results are shown on pg. 6 and 11. [of record]

67. These references are a few examples of many references which the examiner has obtained concerning animation as applied to simulation in general, and sputtering, in particular."

68. **Any inquiry concerning this communication or earlier communications from the examiner should be:**

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directed to:

Dr. Hugh Jones telephone number (703) 305-0023, Monday-Thursday 0830 to 0700 ET, *or* the examiner's supervisor, Kevin Teska, telephone number (703) 305-9704. Any inquiry of a general nature or relating to the status of this application should be directed to the Group receptionist, telephone number (703) 305-3900.

mailed to:

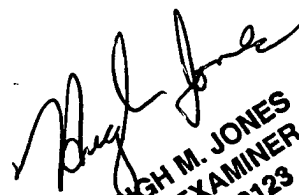
Commissioner of Patents and Trademarks
Washington, D.C. 20231

or faxed to:

(703) 308-9051 (for formal communications intended for entry)

or (703) 308-1396 (for informal or draft communications, please label "*PROPOSED*" or "*DRAFT*").

Dr. Hugh Jones
March 19, 2002


DR. HUGH M. JONES
PATENT EXAMINER
ART UNIT 2123